

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L7	0	10/494249	USPAT	OR	OFF	2007/01/17 10:10
L8	3	10/494249	US-PGPUB; USPAT	OR	OFF	2007/01/17 10:10
L9	0	invention adj provides and polishing adj pad	US-PGPUB; USPAT	OR	OFF	2007/01/17 10:11
L10	1509	elastic adj modulus with mpa	US-PGPUB; USPAT	OR	OFF	2007/01/17 10:12
L11	45	elastic adj modulus with mpa same pad	US-PGPUB; USPAT	OR	ON	2007/01/17 10:30
L12	54	elastic with modulus with mpa same pad	US-PGPUB; USPAT	OR	ON	2007/01/17 10:30
L13	20	elastic with modulus with mpa same pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 12:07
L14	12	compress\$ with elastic with modulus with mpa same pad	US-PGPUB; USPAT	OR	ON	2007/01/17 12:08
L15	10	compress\$4 with elastic with modulus with mpa same pad	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO	OR	ON	2007/01/17 12:10
L16	10	compress\$6 with elastic with modulus with mpa same pad	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO	OR	ON	2007/01/17 12:14
L17	137	modulus with mpa with pad	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO	OR	ON	2007/01/17 12:14
L18	45	compress\$6 same modulus with mpa same pad	US-PGPUB; USPAT	OR	ON	2007/01/17 12:23
L19	33	compress\$6 same modulus with mpa same pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 12:42
L20	35	compress\$6 same modulus with mpa same pad and @ad<="20030206"	US-PGPUB; USPAT; EPO; JPO	OR	ON	2007/01/17 12:41
L21	31	compress\$6 same modulus with mpa and (cmp polish\$4) with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:29
L22	171	compress\$6 same modulus and (cmp polish\$4) with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:30

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L23	51	compress\$6 same modulus same elastic and (cmp polish\$4) with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:32
L24	15860	compress\$6 same modulus elastic same pad and (cmp polish\$4) with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:32
L25	9	compress\$6 same modulus same elastic same pad and (cmp polish\$4) with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:33
L26	4296320	compress\$6 same modulus same elastic same pad \ and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:33
L27	59	compress\$6 same modulus same elastic same pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:35
L28	116	compress\$6 same modulus with elastic\$5 same pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:35
L29	71	compress\$6 same modulus with elastic\$5 with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:35
L30	56	compress\$6 with modulus with elastic\$5 with pad and @ad<="20030206"	US-PGPUB; USPAT	OR	ON	2007/01/17 13:35
S1	6923	polish\$ with pad	USPAT	OR	OFF	2005/10/20 14:44
S2	2301	polish\$ with pad same (cell recess\$ space\$ open\$ void\$empty)	USPAT	OR	OFF	2005/10/20 14:46
S3	2315	polish\$ with pad same (cell or cellular recess\$ space\$ open\$ void\$empty)	USPAT	OR	OFF	2005/10/20 14:46
S4	2478	polish\$ with pad same (cell or cellular recess\$ space\$ open\$ void\$empty matrix)	USPAT	OR	OFF	2005/10/20 14:47
S5	2528	polish\$ with pad same (cell or cellular recess\$ space\$ open\$ void\$ empty matrix)	USPAT	OR	OFF	2005/10/20 14:51
S6	1493	polish\$ with pad with (cell or cellular recess\$ space\$ open\$ void\$ empty matrix)	USPAT	OR	OFF	2005/10/20 15:37
S7	94	polish\$ with pad with (cell or cellular recess\$ space\$ open\$ void\$ empty matrix) and pad with (non adj abrasive or nonabrasive)	USPAT	OR	OFF	2005/10/20 15:40

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S8	61	polish\$ with pad with (cell or cellular recess\$ void\$ empty matrix) and pad with (non adj abrasive or nonabrasive)	USPAT	OR	OFF	2005/10/20 15:42
S9	1	polish\$ with pad with (cell or cellular recess\$ void\$ empty matrix) same (microm meter nanometer meter centimet cm mm milimeter m) and pad with (non adj abrasive or nonabrasive)	USPAT	OR	OFF	2005/10/20 15:46
S10	1	polish\$ with pad with (cell or cellular recess\$ void\$ empty) same (matrix matrix\$4) same (microm meter nanometer meter centimet cm mm milimeter m)	USPAT	OR	OFF	2005/10/20 15:47
S11	25	polish\$ with pad with (cell or cellular recess\$ void\$ empty) same (matrix matrix\$4)	USPAT	OR	OFF	2005/10/20 16:18
S12	1	"2000349053" "349053"	JPO	OR	OFF	2005/10/20 15:59
S13	2	2002/0078632 "0078632"	USPAT	OR	OFF	2005/10/20 16:00
S14	2	2002/0078632 "0078632"	US-PGPUB; USPAT	OR	OFF	2005/10/20 16:01
S15	21627	hasegawa	US-PGPUB; USPAT	OR	OFF	2005/10/20 16:01
S16	1538	hasegawa and pad	US-PGPUB; USPAT	OR	OFF	2005/10/20 16:01
S17	205	hasegawa and pad same polish\$	US-PGPUB; USPAT	OR	OFF	2005/10/20 16:04
S18	40	hasegawa.inv. and pad same polish\$	US-PGPUB; USPAT	OR	OFF	2005/10/20 16:04
S19	5	("3504457" "6354915" "6419556" "6517426").PN. OR ("6848974").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/20 16:49
S20	2313	(poros porous porosity) and polish\$4 with pad	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/20 16:50
S21	988	(poros porous porosity pore void cavity) same (size length volume) and polish\$4 with pad	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/20 16:51
S22	588	(poros porous porosity pore void cavity) with (size length volume) and polish\$4 with pad	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/20 16:51
S23	477	(poros porous porosity pore void cavity) with (size length volume) and polish\$4 adj pad	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/20 17:13

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S24	173	(poros porous porosity pore void cavity) with (size length volume) and polish\$4 adj pad and (poros porous porosity pore void cavity) with volume and (cmp or semiconductor or cheical adj mechanical)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/21 08:01
S25	27	("6062968").URPN.	USPAT	OR	OFF	2005/10/21 08:05
S26	1	("6790883").URPN.	USPAT	OR	OFF	2005/10/21 10:27
S27	8	("20020173231" "20030060138" "20030129931" "20040014413" "20040063391" "20040118051" "6645264" "6790883").PN. OR ("6903021").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/10/21 10:59
S28	1	("2002/0098789").URPN.	USPAT	OR	OFF	2005/10/21 13:30
S29	73	"438"/\$.ccls. and copper with damascene and (polyarylene polysiloxane methylsilsesquioxane) and (sin sioc nitride oxide)	USPAT	OR	OFF	2005/10/21 16:05
S30	68	"438"/\$.ccls. and copper with damascene and (polyarylene polysiloxane methylsilsesquioxane) and (sin sioc nitride oxide) with layer	USPAT	OR	OFF	2005/10/21 16:05
S31	31	"438"/\$.ccls. and copper with damascene and (polyarylene polysiloxane methylsilsesquioxane) and (sin sioc nitride oxide) with layer same (cmp or polish\$)	USPAT	OR	OFF	2005/10/21 16:47
S32	1622	"438"/\$.ccls. and trench with isolation same polish\$	USPAT	OR	OFF	2005/10/21 16:49
S33	1216	"438"/\$.ccls. and trench with isolation same polish\$ same (oxide or sog or glass)	USPAT	OR	OFF	2005/10/21 17:00
S34	860	"438"/\$.ccls. and trench with isolation same polish\$ same (oxide or sog or glass) same substrate	USPAT	OR	OFF	2005/10/21 17:01
S35	649	"438"/\$.ccls. and trench with isolation same polish\$ same (oxide or sog or glass) same substrate with trench	USPAT	OR	OFF	2005/10/21 17:01
S36	1508	polish\$ with pad and volume	USPAT	OR	OFF	2006/03/24 15:16
S37	273	polish\$ with pad and volume with particle	USPAT	OR	ON	2006/03/24 15:16
S38	49	polish\$ with pad and volume with particle same (percent\$ fraction)	USPAT	OR	ON	2006/03/24 15:42

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S39	1587	polish\$ with pad and pad with compos\$	USPAT	OR	ON	2006/03/24 15:43
S40	444	"438"/\$.ccls. and polish\$ with pad and pad with compos\$	USPAT	OR	ON	2006/03/24 15:43
S41	140	"438"/\$.ccls. and polish\$ with pad and pad with compos\$ same particl\$	USPAT	OR	ON	2006/03/24 15:44
S42	148	"438"/\$.ccls. and polish\$ with pad and pad with compos\$ same (solub\$ particl\$)	USPAT	OR	ON	2006/03/24 15:50
S43	19	"438"/\$.ccls. and polish\$ with pad and pad with compos\$ same (solub\$)	USPAT	OR	ON	2006/03/24 16:25
S44	12	"438"/\$.ccls. and polish\$ with pad and pad with compos\$ same (solub\$)	US-PGPUB	OR	ON	2006/03/24 17:20
S45	0	"5702977".pn. "6663787".pn.	US-PGPUB	OR	ON	2006/03/24 17:21
S46	2	"5702977".pn. "6663787".pn.	US-PGPUB; USPAT	OR	ON	2006/03/24 17:34
S47	3	"5702977".pn. "6663787".pn. "6953388".pn.	US-PGPUB; USPAT	OR	ON	2006/03/24 17:55
S48	1	("5702977".pn. "6663787".pn. "6953388".pn.) and substrate same polish\$ same slurry	US-PGPUB; USPAT	OR	ON	2006/03/27 10:56
S49	1	("5702977".pn. "6663787".pn. "6953388".pn.) and abrasive same slurry	US-PGPUB; USPAT	OR	ON	2006/03/27 10:56
S50	0	"10771060"	USPAT	OR	OFF	2007/01/16 16:17
S51	0	"10/771060"	USPAT	OR	OFF	2007/01/16 16:17
S52	1	"10/771060"	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:29
S53	10	"6953388" 2002/0098789 "6531399"	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:30
S54	5	"6953388".PN. "2002/0098789" "6531399".pn.	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:30
S55	3	"6953388".PN. "10/053892" "6531399".pn.	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:31
S56	64	compression adj elastic adj modulus	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:32
S57	3	compression adj elastic adj modulus same pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:57
S58	18	compression adj elastic adj modulus same mpa	US-PGPUB; USPAT	OR	OFF	2007/01/16 16:33
S59	9	compression adj elastic adj modulus same mpa and pad	US-PGPUB; USPAT	OR	ON	2007/01/16 16:39

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S60	51	compressibility same mpa and pad	US-PGPUB; USPAT	OR	ON	2007/01/16 16:39
S61	19	compressibility same mpa same pad	US-PGPUB; USPAT	OR	ON	2007/01/16 16:39
S62	15	compression adj elastic adj modulus and pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:02
S63	34	compress\$ adj elastic adj modulus and pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:03
S64	345825	compress\$ adj elastic adj modulus same mpaand pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:03
S65	9	compress\$ adj elastic adj modulus same mpa and pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:15
S66	6	compress\$ adj elastic adj modulus same pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:16
S67	22	compress\$ with elastic adj modulus same pad	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:16
S68	12	compress\$ with elastic adj modulus same pad same mpa	US-PGPUB; USPAT	OR	OFF	2007/01/16 17:16
S69	12	compress\$ with elastic adj modulus same pad same mpa	US-PGPUB; USPAT	OR	ON	2007/01/16 17:16